# LabAdviser update: 10/11 2023

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| Updated Subject | Contributor | Link to the updated pages |
| E-beam page has been redone over the last couple of months. | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography> |
| E-beam: New booking guide to JEOL 9500 users | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/JEOLRequest> |
| E-beam: Tutorial/introduction to new JEOL 9500 users | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/FirstEBL> |
| E-beam: Overview of all cassettes to JEOL 9500 | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/Cassettes> |
| E-beam: Wafer alignment on the JEOL 9500 system | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/JEOLAlignment> |
| E-beam: guide to Beamer (Still work in progress) | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/BEAMER> |
| E-beam: description of different strategies/setups of dose tests on the JEOL 9500 | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/Dose_Testing> |
| E-beam: A list of all cyclic calibration routines (path) on the JEOL 9500 | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/EBeamLithography/FilePreparation/Pathlist> |
| Mix of Lithography: Description of mix-and-match lithography between UVL and EBL | **Thomas Pedersen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/Mix-and-match> |
| This page about Aligner: Maskless 02 (MLA2) was updated to reflect the change to write mode 2, especially in the sections “Process Parameters” and “Alignment”. | **Thomas Aarøe Anhøj and Jens Hemmingsen @Nanolab** | [Specific Process Knowledge/Lithography/Aligners/Aligner: Maskless 02 processing - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/Aligners/Aligner:_Maskless_02_processing) |
| Maskless aligner 01: Important note added on alignment on this aligner (this was added in June) | **Thomas Aarøe Anhøj @Nanolab** | [https://labadviser.nanolab.dtu.dk//index.php?title=Specific\_Process\_Knowledge/Lithography/Aligners/Aligner:\_Maskless\_01\_processing#Alignment](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/Aligners/Aligner:_Maskless_01_processing#Alignment) |
| Developer: TMAH Manual  Changes related to the modification from spray nozzle dispense to puddle dispense | **Jens Hemmingsen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/Development#Developer:_TMAH_Manual> |
| Developer: SU-8 (wetbench)  Section created as new tool is installed in cleanroom (work in progress) and included in the overview table. | **Jens Hemmingsen @Nanolab** | <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/Development#Developer:_SU8_(wetbench)>  <https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Lithography/Development#Development_Comparison_Table> |
| ALD: Deposition of TiO2 with ALD – page has been rewritten. | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Thin film deposition/ALD Picosun R200/TiO2 deposition using ALD - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/ALD_Picosun_R200/TiO2_deposition_using_ALD) |
| ALD: Deposition of Al2O3 with ALD – page has been rewritten. | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Thin film deposition/ALD Picosun R200/Al2O3 deposition using ALD - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/ALD_Picosun_R200/Al2O3_deposition_using_ALD) |
| Cluster Lesker PC3 Src3: Tungsten (W) deposition using High Power Impulse Magnetron Sputtering (HiPIMS) | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Thin film deposition/Deposition of Tungsten/HiPIMS Sputtering of W in Sputter-system Metal-Nitride (PC3) - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Tungsten/HiPIMS_Sputtering_of_W_in_Sputter-system_Metal-Nitride_(PC3)) |
| Cluster Lesker PC3 Src2: Deposition of Al | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Thin film deposition/Deposition of Aluminium/Al Sputtering in Cluster Lesker PC3 - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Aluminium/Al_Sputtering_in_Cluster_Lesker_PC3) |
| Cluster Lesker PC3: Deposition of NbTiN | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Thin film deposition/Deposition of Niobium Titanium Nitride/NbTiN Reactive p-DC Sputtering in Cluster Lesker PC3 - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Niobium_Titanium_Nitride/NbTiN_Reactive_p-DC_Sputtering_in_Cluster_Lesker_PC3) |
| Cluster Lesker PC3 Src1: Deposition of Scandium and Scandium nitride | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Thin film deposition/Deposition of Scandium/Sc Sputtering in Cluster Lesker PC3 - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Scandium/Sc_Sputtering_in_Cluster_Lesker_PC3)  [Specific Process Knowledge/Thin film deposition/Deposition of Scandium Nitride/ScN Reactive Sputtering in Cluster Lesker PC3 - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Scandium_Nitride/ScN_Reactive_Sputtering_in_Cluster_Lesker_PC3) |
| New equipment page:  CRAIC Microspectrophotometer | **Evgeniy Shkondin @Nanolab** | [Specific Process Knowledge/Characterization/MicroSpectroPhotometer (Craic 20/30 PV) - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Characterization/MicroSpectroPhotometer_(Craic_20/30_PV)) |
| Dry etch: DRIE Pegasus 4 (6” oxide and nitride etcher)   * A little data was added during this year on nitride etching. * At present I am working on SiO2 etching with Cr mask. Some images are added here (this is work in progress): | **Berit Herstrøm @Nanolab** | [Specific Process Knowledge/Etch/DRIE-Pegasus/Pegasus-4 - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Etch/DRIE-Pegasus/Pegasus-4)  [Specific Process Knowledge/Etch/DRIE-Pegasus/Pegasus-4/SiO2 Etch/Cr mask - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Etch/DRIE-Pegasus/Pegasus-4/SiO2_Etch/Cr_mask) |
| Dry etch: ASE: Some new recipes for SiO2 and silicon nitride etching as the old recipes became unstable. This is still being worked on. | **Maria Farinha @Nanolab** | [Specific Process Knowledge/Etch/Etching of Silicon Oxide/SiO2 etch using ASE - LabAdviser (dtu.dk)](https://labadviser.nanolab.dtu.dk/index.php?title=Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_ASE) |